

IMPURITY INTRODUCING APPARATUS AND IMPURITY INTRODUCING METHOD

Abstract

When impurities before introduction in solid specimens are mixed with each other, originally expected functions would not be fully exerted. It is intended to prevent the mixing and to realize a high-precision plasma doping. For screening impurities that may be mixed from impurities not to be mixed, first, core impurity introduction means is screened. Further, for avoiding any minute-amount mixing, not only transport means for semiconductor substrate as a treatment object but also means for removing a resin material provided on the semiconductor substrate is specialized so as to effect mixing prevention.

FIG. 1